

Title (en)

COLD-PRESSED SPUTTER TARGETS

Title (de)

KALTGEPRESSTE SPUTTERTARGETS

Title (fr)

CIBLES DE PULVÉRISATION CATHODIQUE COMPACTÉES À FROID

Publication

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Application

EP 07725645 A 20070530

Priority

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Abstract (en)

[origin: WO2007137824A1] The invention relates to a sputter target comprising a sputter material that is made of an alloy or a material mixture composed of at least two components which are in a state of thermodynamic disequilibrium. According to the invention, the components are compacted by means of an isostatic or uniaxial cold-pressing process.

IPC 8 full level

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